

IN THE SPECIFICATION:

Page 1, before the first paragraph, insert the heading:

C1 **--Field and Background of the Invention--**.

Page 4, before the first paragraph, insert the heading:

C2 **--Summary of the Invention--**.

Page 13, amend the paragraph beginning on line 13 to read:

C3 ~~Further preferred embodiments of the vacuum treatment installation according to the invention as well as of the ultrahigh vacuum CVD reactor according to the invention are apparent to a person skilled in the art on the basis of the following description of examples and are in particular specified in claims 23 to 45.--~~

Page 13, before the paragraph beginning on line 23, insert the heading:

C4 **--Brief Description of the Drawings--**.

Page 15, before the paragraph beginning on line 1, insert the heading:

C5 **--Description of the Preferred Embodiments--**.

Page 29, amended the paragraph beginning on line 5 to read:

C6 ~~With the methods according to the invention, the vacuum treatment installation according to the invention or the UHV-CVD reactor according to the invention, structural members are produced by [[eliminate return]] deposition of atom monolayers (atomic layer deposition) or by deposition of epitactic layers or by coating of deep-profiled surfaces, such~~

as surfaces with so-called deep trenches.--.

C6

